

INFORMATION DISCLOSURE CITATION IN AN APPLICATION			ATTY. DOCKET NO. 60188-063	SERIAL NO.			
			APPLICANT Bunji MIZUNO, et al.				
(PTO-1449)			FILING DATE April 24, 2001	GROUP			
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
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	Gibilisco, "Encyclopedia of Electronics", TAB Professional and Reference Books, pp. 30-31 (1985)						
AICS	K.C. Walter et al., Materials Research Bulletin, 29 (1994) 827						
EXAMINER <i>Ascole Munay Surkar</i>	DATE CONSIDERED <i>3/19/02.</i>						

JC971 U.S. PRO
 06/840306
 04/24/01

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INFORMATION DISCLOSURE
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APPLICATION

(PTO-1449)



ATTY. DOCKET NO.
60188-063

SERIAL NO.
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APPLICANT

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U.S. PATENT DOCUMENTS

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FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
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EXAMINER

Asok Kumar Sarker

DATE CONSIDERED

3/19/52

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